

Notice of References Cited	Application/Control No. 10/679,844		Applicant(s)/Patent Under Reexamination STOKOWSKI ET AL.	
	Examiner Michael P. Stafira		Art Unit 2877	Page 1 of 1

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*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Name	Classification
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	C	US-6,184,976	02-2001	Park et al.	356/237.4
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NON-PATENT DOCUMENTS

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	U	Anton Barty, "Aerial Image Microscopes for the inspection of defects in EUV masks" 2002, 22 nd Annual BACUS Symposium on Photomask Technology, SPIE VOL. 4889 (2002).				
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*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)
Dates in MM-YYYY format are publication dates. Classifications may be US or foreign.